

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of: )  
)  
Mari INOUE ) Parent Group Art Unit: 2813  
)  
Rule 1.53(b) Division of Application No. ) Parent Examiner: C. Thompson  
10/107,247 filed March 28, 2002 )  
)  
Filed: Herewith )  
)  
For: A METHOD FOR CORRECTING )  
A DESIGN DATA OF A LAYOUT )  
PATTERN OF A PHOTOMASK, )  
PHOTOMASK )  
MANUFACTURING BY SAID )  
METHOD, AND )  
SEMICONDUCTOR DEVICE )  
METHOD USING SAID )  
PHOTOMASK )

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**PRELIMINARY AMENDMENT**

Please amend the above-identified patent application as follows:

**Amendments to the Specification** are included in this paper.

**Amendments to the Claims** are reflected in the listing of claims in this paper.

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